

UNITED STATES PATENT AND TRADEMARK OFFICE
CERTIFICATE OF CORRECTION

PATENT NO. : 7,535,220 B2
APPLICATION NO. : 10/597838
DATED : May 19, 2009
INVENTOR(S) : Yuichiro Sasaki et al.

Page 1 of 2

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

In Column 2, line 58, please delete “cannot” and insert --can not--.

In Column 3, line 61, please delete “maybe” and insert --may be--.

In Column 3, line 62, please delete “maybe” and insert --may be--.

In Column 12, line 31, please delete the text beginning in Column 12, line 31 and ending in Column 12, line 55, and insert therefor

--9. The beam measuring method according to claim 8, wherein the beam current value of the beam line and the beam position are simultaneously measured.

10. A beam control method comprising; a measurement step which measures a beam current of beams which are generated by an ion source or an electron beam source using the beam measuring method described in claim 8; and a control step which feedbacks the beam current value and positions of beams which are obtained by the measuring step or both of the beam current value and the positions of beams to control parameters of the ion source, the electron beam source, an analysis electric magnet, a part for applying an electric field and a magnetic field to beams.

11. The beam control method according to claim 10, wherein the beam radiation method includes a radiation step which radiates the beam current which is controlled using the control parameters obtained in the control step of the beam in claim 12 to a material to be treated.

12. A beam radiation device which includes the beam measuring device described in claim 1.

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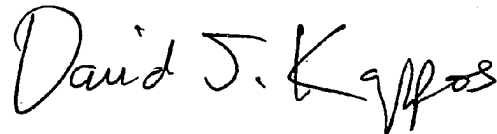
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It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

13. A material to be treated which is manufactured or inspected casing an ion injection device, an electronic beam exposure device, an accelerator or an electron beam vapor deposition device which includes the beam measuring device described in claim 1.--.

Signed and Sealed this

Twenty-fifth Day of August, 2009

A handwritten signature in black ink, reading "David J. Kappos". The signature is written in a cursive, flowing style with a large initial "D" and a stylized "K".

David J. Kappos
Director of the United States Patent and Trademark Office